

(b) Amendment to the Claims

Please cancel claims 6, 8, 12-14, 20, 22 and 26-30 without prejudice or disclaimer of subject matter.

Kindly amend claims 1, 10, 11, 15, 24 and 25 as follows. A detailed listing of all the claims is provided.

1. (Currently Amended) An exhaust processing method of exhausting a processing space for subjecting a substrate or a film to ~~plasma processing with plasma~~, which comprises:

(a) providing a chemical-reaction inducing unit~~means~~ having a heating element comprising a first metal member in an exhaust line, said exhaust line connecting the processing space and an exhaust unit~~means~~ for exhausting the processing space, wherein the first metal member is connected to a power source;

(b) providing a plasma blocking unit~~means~~ consisting of a second metal member electrically grounded between the processing space and the first metal member; wherein the chemical-reaction inducing unit is provided at a position where the plasma reaches and the plasma blocking unit blocks the plasma from reaching the chemical-reaction inducing unit; and

(c) causing chemical reaction of at least either an unreacted gas or a by-product exhausted from the processing space via heat from said heating element while ~~blocking plasma in the processing space from reaching the chemical-reaction inducing means via said plasma blocking means~~ unit acts to reduce electron number density in the plasma reaching the chemical-reaction inducing unit by at least 90%.

2. - 9. (Cancelled)

10. (Currently Amended) The exhaust processing method according to claim 1, wherein one or more linear members or a linear member formed by a spiral winding are used as the unitmeans for blocking plasma.

11. (Currently Amended) The exhaust processing method according to claim 1, wherein a mesh is used as the unitmeans for blocking plasma.

12.-14. (Cancelled)

15. (Currently Amended) A plasma processing method for subjecting a substrate or a film to ~~[[plasma]]~~ processing with plasma, which comprises:

(a) arranging a chemical-reaction inducing unitmeans having a heating element comprising a first metal member in an exhaust line, said exhaust line connecting a processing space for plasma processing and an exhaust pumpmeans for exhausting the processing space, wherein the first metal member is connected to a power source;

(b) providing a plasma blocking unitmeans consisting of a second metal member electrically grounded between the processing space and the first metal member; wherein the chemical reaction inducing unit is provided at a position where the plasma reaches and the plasma blocking unit blocks the plasma from reaching the chemical reaction inducing unit; and

(c) causing chemical reaction of at least either an unreacted gas or a by-product exhausted from the processing space via heat from said heating element while ~~blocking plasma in the processing space from reaching the chemical reaction inducing means via~~ said plasma blocking ~~means~~ unit acts to reduce electron number density in the plasma reaching the chemical-reaction inducing unit by at least 90%.

16. - 23. (Cancelled)

24. (Currently Amended) The plasma processing method according to claim 15, wherein one or more linear members or a linear member formed by a spiral winding are used as the unit~~means~~ for blocking plasma.

25. (Currently Amended) The plasma processing method according to claim 15, wherein a mesh is used as the unit~~means~~ for blocking plasma.

26. - 50. (Cancelled)